

Process type factors	Gas <i>i</i>								
	CF ₄	C ₂ F ₆	CHF ₃	CH ₂ F ₂	C ₃ F ₈	c-C ₄ F ₈	NF ₃ remote	NF ₃	SF ₆
Etch 1-U _i	0.6	N/A	0.2	N/A	N/A	0.1	N/A	N/A	0.3
Etch P _{CF₄}	N/A	N/A	0.07	N/A	N/A	0.009	N/A	N/A	N/A
Etch P _{CHF₃}	N/A	N/A	N/A	N/A	N/A	0.02	N/A	N/A	N/A
Etch P _{C₂F₆}	N/A	N/A	0.05	N/A	N/A	N/A	N/A	N/A	N/A
CVD 1-U _i	N/A	N/A	N/A	N/A	N/A	N/A	0.03	0.3	0.9